



In re Application of Cecile BERNE et al.  
Application No.: 10/733,431; Filed: December 10, 2003  
Group Art Unit: 2826; Examiner: Evan T. Pert  
Confirmation No.: 2144; Atty. Dkt. No.: 4717-5499  
TWO-STAGE ANNEALING METHOD FOR MANUFACTURING  
SEMICONDUCTOR SUBSTRATES  
Replacement Sheet

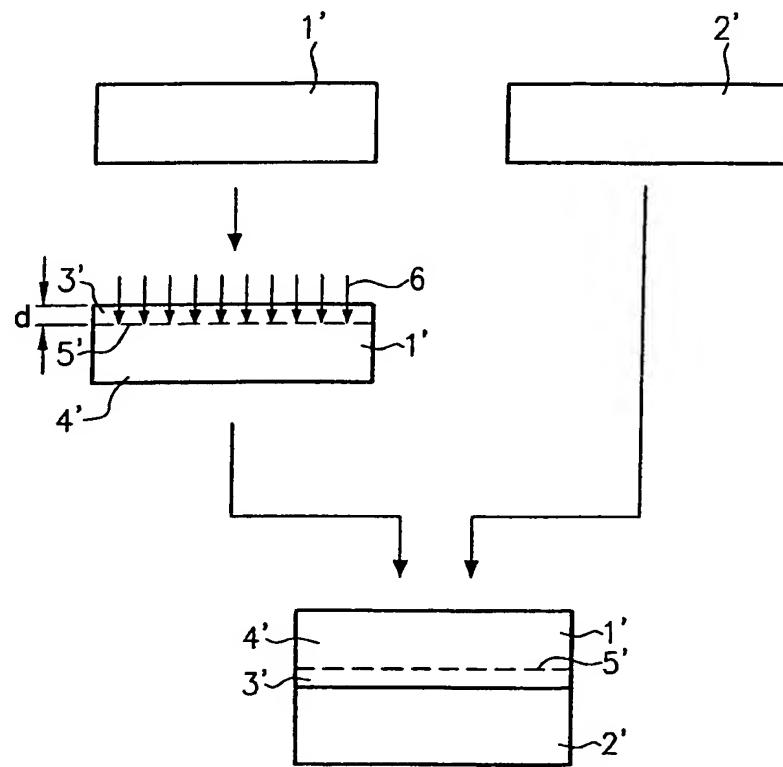


Fig. 6 Prior Art

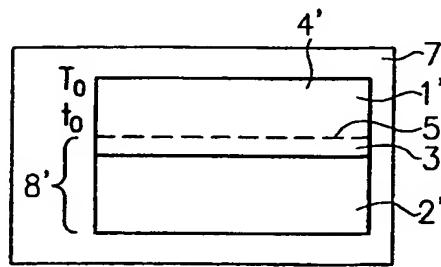


Fig. 7 Prior Art